

L Number	Hits	Search Text	DB	Time stamp
1	124	(((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/09/01 15:51
2	11	((((((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet) and (driver or mover) ) and stator) and (magnetic adj pole)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/09/01 15:54
-	2492	(exposure adj apparatus) and lithography	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/09/01 15:50
-	1852	((exposure adj apparatus) and lithography) and stage	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:29
-	1783	((exposure adj apparatus) and lithography) and stage) and (mask or reticle)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:29
-	2134	((exposure adj apparatus) and lithography) and (stage or table)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:29
-	2020	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:29
-	1362	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:30
-	1342	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/24 15:15
-	170	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:32
-	206	((exposure adj apparatus) and lithography) and (stage or table)) and (reaction near4 force)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:32
-	118	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/18 16:32
-	100	((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/09/01 15:51
-	9	((((((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet) and (driver or mover) ) and stator) and (magnetic adj pole)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/09/01 15:52

-	24	((((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet) and (driver or mover) ) and stator	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/24 15:14
-	56	((((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet) and (driver or mover)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/24 13:54
-	5	((((((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction near4 force)) and electromagnetic) and magnet) and (driver or mover)) and canceling	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/24 13:55
-	6	((((exposure adj apparatus) and lithography) and (stage or table)) and (mask or reticle)) and illumination) and (wafer or specimen or sample)) and (reaction adj cancel\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/24 15:25